FORTEX

MICROTRAK

PROCESSING INSTRUCTIONS

With Microtrak Pre-Sensitive PCB material it is very important to ensure that you have a good opaque artwork which blocks out UV light. This can be achieved with an inkjet A4 or A3 Printer and Jetstar premium film.

PPP-A4100 JETSTAR PREMIUM A4 10 SHEET PACK PPP-A4101 JETSTAR PREMIUM A4 100 SHEET PACK

PPP-A3100 JETSTAR PREMIUM A3 10 SHEET PACK PPP-A3101 JETSTAR PREMIUM A3 100 SHEET PACK

Alternatively if you wish to use a laser printer then we would recommend our LaserStar film

CPP-L4100 Laserstar Film (A4) (10 Shts) CPP-L4101 Laserstar Film (A4) (100 Shts) CPP-L3100 Laserstar Film (A3) (10 Shts) CPP-L3101 Laserstar Film (A3) (100 Shts)

Microtrak PCB material should be processed as follows:

1) Mix the developer as follows:

4007 Photoresist universal powder developer part no: 50G-DEV Add 50 grams of the powder to 1 litre of hot tap water. Stir the powder until it has all dissolved in the water. Allow the developer to cool down to room temperature and use between 18 and 25°C.

4006 liquid photoresist developer concentrate part no: 1L-MICROTRAK Add 80 ml of developer concentrate to 920ml of water to make 1 litre of working solution. Use between 18 and 25°C.

2) Exposing the Board.

It is very important to ensure that the board is fully exposed. Typically we recommend exposure times of $2\frac{1}{2} - 3\frac{1}{2}$ minutes in our UV-AS2436 4 tube exposure unit and $1\frac{1}{2}-2\frac{1}{2}$ minutes in all our other exposure units using our clear inkjet film. However if you are using a more opaque film such as tracing paper or even ordinary paper exposure times will need to be longer. This would have to be determined by trial and error. NB if the resist is not exposed for long enough it will be difficult to develop it all away.

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N.B. Always ensure the exposure unit has been warmed up before using it order to ensure the tubes are giving their maximum output of UV light.

3) Developing

Place the board in the developer and leave for 30 to 90 seconds depending on the temperature of the developer. N.B. the higher the temperature the quicker the development. Agitate the board in the developer every few seconds to ensure even development. The developer should be used between 18 and 25 degrees C.

4) Remove the board from the developer and rinse thoroughly.

Tip for checking board after first exposure and development

To ensure the board has been exposed and developed properly place the board in the ferric chloride for 30 to 60 seconds then rinse thoroughly. All the areas of copper that have been developed away should have turned a dull matt pink colour. If there are any areas which are a shiny gold colour it means that the board has not been exposed for long enough or the developer needs replacing. In this case put the board back into the developer for another 20-30 seconds then remove it and rinse immediately. Place the board in the ferric chloride solution for another 30 to 60 seconds and check as before.

5) Strip the resist

After etching the photoresist can be stripped off using our PC155 stripper or solvent such as our universal solvent or acetone.

Chemistry

50G-DEV	4007S005 Seno Universal Developer 500g makes 10 Ltrs
1L-MICROTRAK	4006V05 Seno Liquid Dev conc 1Ltr makes 12.5 litres
RESIS-STR	PC155 Resist Strip 1 Ltr makes 5 Ltrs
50ML-SL	Universal Solven t
5L-FERRIC	(5LTR) Liquid Ferric Chloride Etchant *UK ONLY